

Electronic Patent Application Fee Transmittal

Application Number:	10587194
Filing Date:	24-Jul-2006
Title of Invention:	Protected pattern mask for reflection lithography in the extreme uv or soft x-ray range
First Named Inventor/Applicant Name:	Jean-Louis Stehle
Filer:	Peter C. Hsueh/Robin Ford
Attorney Docket Number:	58059/N75

Filed as Large Entity

U.S. National Stage under 35 USC 371 Filing Fees

Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
Basic Filing:				
Pages:				
Claims:				
Miscellaneous-Filing:				
Petition:				
Patent-Appeals-and-Interference:				
Post-Allowance-and-Post-Issuance:				
Extension-of-Time:				
Extension - 3 months with \$0 paid	1253	1	1110	1110

Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
Miscellaneous:				
Total in USD (\$)				1110